

## Paper List

*January –December, 2025*

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- E2025-1(F) Metal Contamination Behavior on Silicon Dioxide Surface Rinsed With Deionized Water Containing Ultra-Trace Metal During Single-Wafer Cleaning  
IEEE Transactions on Semiconductor Manufacturing, Vol.38, No.3, (2025), pp.492-498  
K. Tsutano, T. Mawaki, Y. Shirai, R. Kuroda  
DOI: [10.1109/TSM.2025.3575743](https://doi.org/10.1109/TSM.2025.3575743)
- E2025-2(C) On the determination threshold of illumination-adaptive signal selection technology for multi-stage LOFIC CMOS image sensors  
2025 International Image Sensor Workshop (IISW2025), pp.61-64, R02.5, June 2, (2025), Hyogo  
Yoshihito Hirai, Kohei Takizawa, Takezo Mawaki, Rihito Kuroda  
DOI: <https://doi.org/10.60928/wjde-as5j>
- [E2025-3\(C\)](#) Statistical Capacitance Measurement of Si Trench Capacitors Using Array Test Circuit  
Extended Abstracts of the 2025 International Conference on Solid State Devices and Materials (SSDM2025), pp.165-166, C-1-03, September 16, (2025), Yokohama  
Ryoya Nishimaki, Koga Saito, Takezo Mawaki, Ken Miyauchi, Rihito Kuroda
- [E2025-4\(C\)](#) [Invited]  
Progress in Development of Advanced High Dynamic Range CMOS Image Sensors  
PROCEEDINGS OF THE INTERNATIONAL DISPLAY WORKSHOPS, VOL. 32, 2025 (IDW '25), pp. 1612-1615 (IST1-1) December 4, Hiroshima  
Ken Miyauchi  
[https://pub-files.atlas.jp/fs/public/idw2025/ver\\_14/abstract/en/IST1-01.pdf](https://pub-files.atlas.jp/fs/public/idw2025/ver_14/abstract/en/IST1-01.pdf)